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	AA						
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FOREIGN PATENT DOCUMENTS

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							Yes	No
PN	AF	WO 01/27063 A1	04/04/02	WIPO				
	AG							

OTHER REFERENCES (including Author, Title, Date, Periodical Pages, Etc.)

H	AH		"Atomic Layer Deposition of SiO ₂ Using Catalyzed And Uncatalyzed Self-Limiting Surface Reactions"; J.W. Klaus et al; Surface Review					
			and Letters, Vol. 6, Nos. 3 & 4 (1999) pp. 435-448					
	AI		Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy)silanol; K.A. Miller et al;					
			Thin Solid Films 397 (2001); pp. 78-82					
	AJ		"Reactive Deposition of Metal Thin Films within Porous Supports from Supercritical Fluids"; Neil E. Fernandes et al; Chem Mater. 2001;					
			13, pp. 2023-2031					
	AK		"Supercritical CO ₂ Processing for Submicron Imaging of Fluoropolymers"; Narayan Sundararajan et al; Chem. Mater. 2000;					
			pg. 41-48					
	AL		"Supercritical carbon dioxide assisted aerosolization for thin film deposition, fine powder generation, and drug delivery";					
			C.Y. Xu et al; P.T. Anastas; T.C. Williamson, Green Chemistry, 5, pp. 313-335; Oxford University Press, Oxford 1998					
H	AM		"Supercritical Fluid Transport-Chemical Deposition of Films"; Brian N. Hansen et al; Chem Mater. 1992; 4; pp. 749-752					

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